



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Andrei V. Shchegrov
Title: Parametric Profiling Using Optical Spectroscopic Systems
Application No.: 09/741,663 Filing Date: December 19, 2000
Examiner: Roy M. Punnoose Group Art Unit: 2877
Docket No.: TNCR.189US0 Conf. No.: 7526

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 to the Examiner's attention in this patent application.

Copies of the documents listed on the accompanying Form PTO-1449 are enclosed.

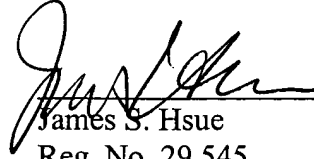
Citation of these documents shall not be construed as (1) an admission that the documents are prior art with respect to the invention or inventions claimed in this application, (2) a representation that a search has been made (other than as indicated by any cited document), or (3) an admission that the cited information is, or is considered to be, material to patentability as defined in § 1.56(b).

This information disclosure statement is submitted under 37 C.F.R. § 1.97(b) and consequently no fee should be required. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

EXPRESS MAIL NO.:

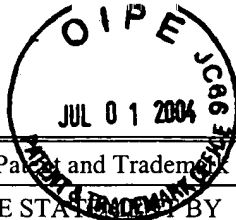
EV437667898US

Respectfully submitted,


James S. Hsue

Reg. No. 29,545

6/30/04
Date



U.S. Department of Commerce, Patent and Trademark	Atty. Docket No.	Application No.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	TNCR.189US0	09/741,663
(Use several sheets if necessary)	Applicant(s)	Conf. No.
	Andrei V. Shchegrov	7526
	Filing Date	Group
	December 19, 2000	2877

U.S. Patent Documents

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

Foreign Patent Documents

							Translation	
	Document	Date	Country	Class	Subclass	Yes	No	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

1	Patent Search conducted on August 1, 2000
2	"Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features," N. Blayo et al., <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 3, March 1995, pp. 591-599.
3	"Algorithm Implementation and Techniques for Providing More Reliable Overlay Measurements and Better Tracking of the Shallow Trench Isolation (STI) Process," D. Schramm et al., <i>SPIE: Conference on Metrology, Inspection, and Process Control of Microlithography XIII</i> , March 1999, pp. 116-122.

Examiner

Date Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.